



FRAUNHOFER INSTITUTE FOR INTEGRATED SYSTEMS AND DEVICE TECHNOLOGY IISB

#### **APPLICATIONS**

- Wafer handling studies
- Robot assessment
- End effector assessment
- Equipment assessment
- Equipment development

#### **CONTACT**

Fraunhofer Institute for Integrated Systems and Device Technology IISB Schottkystrasse 10 91058 Erlangen, Germany

www.iisb.fraunhofer.de

Dr. Martin Schellenberger Phone: +49 9131 761 222 Fax: +49 9131 761 72222

E-mail: martin.schellenberger@iisb.fraunhofer.de

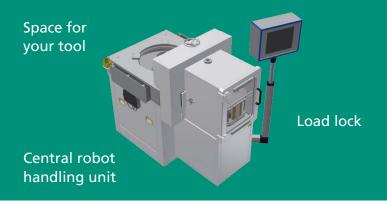


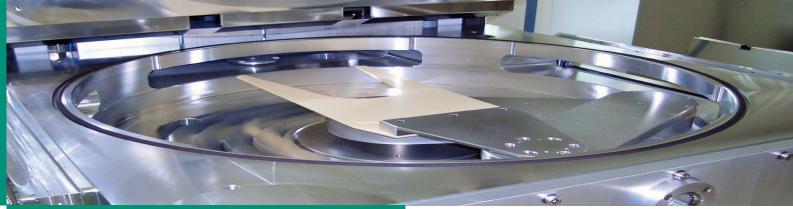
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# HANDLING PLATFORM FOR 450 MM WAFERS



A PLATFORM FOR EQUIPMENT R&D AND ASSESSMENT





## R&D AND ASSESSMENT FOR 450 MM EQUIPMENT

The 450 mm cluster platform at Fraunhofer IISB provides a unique opportunity for equipment suppliers to assess and / or develop 450 mm semi-conductor equipment without having to concern themselves with automation and wafer handling.

You are preparing demonstrator equipment for 450 mm processing or metrology? You are about to take a first step into 450 mm modules? You develop components or OEM parts for 450 mm equipment?

We offer you a playground and substantial support for 450 mm research, development, test, and assessment in our industry-compliant environment.

Fraunhofer IISB 450 mm R&D cluster platform – your opportunity to bring your core competence to market

## SPECIFICATIONS OF THE CLUSTER PLATFORM

- 450 mm and 300 mm wafer handling without retrofitting
- Pressure range from atmospheric to high vacuum (10<sup>-7</sup> Torr)
- Transport Max Reach (TMR) of the central robot: 545 mm
- Wafer Transfer Plane (WTP) is variable between 1100 mm and 1400 mm
- Vacuum alignment tunnel and cooling station integrated
- Versatile metrology module to evaluate metrology components (in development)

### DEVELOPMENT SUPPORT AT FRAUNHOFER IISB

Fraunhofer IISB has outstanding experience in the field of semiconductor equipment development and assessment.

### Fraunhofer IISB supports you with:

- Cleanroom facilities up to class 10
- Various capabilities for measurement and characterization
- Accredited analysis laboratory for micro and nanotechnology
- Possibility of resizing 450 mm wafers to 300 mm or below in order to fit measurement equipment or subsequent process equipment